Kraig J. Andrews

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Education

• Wayne State University

Detroit, MI

Department of Physics & Astronomy, Ph.D. Physics

2014 - Present

- Advisor: Dr. Zhixian Zhou
- Thesis Title: "Quantum Transport Properties and Scattering Mechanisms in Transition Metal Dichalcogenides"

• Wayne State University

• Michigan State University

Detroit, MI, U.S.A.

2017

Department of Physics & Astronomy, M.Sc. Physics

East Lansing, MI, U.S.A.

Department of Physics & Astronomy, B.Sc. Physics

East Lansing, MI, U.S.A.

• Michigan State University Department of Physics & Astronomy, B. Astrophysics. Sc

2014

Experience

 Nano Fabrication & Electron Transport Laboratory Graduate Research Assistant

Wayne State University, Detroit, MI, U.S.A.

2015 – Present

- Fabricate field-effect transistors using two-dimensional semiconductors to invesitgate their intrinsic transport properties.
- Develop novel techniques for making low-resistance Ohmic contacts to a wide variety of two-dimensional semiconductors.
- National Institute of Materials Science

Tsukuba, Ibaraki Prefecture, Japan

Visiting Graduate Researcher, Summer Intern

- Investigate methods for surface modification of two-dimensional semiconductors for the use of creating a new low-resistance Ohmic contact strategy.
- Interational Course on Computational Physics Undergraduate Researcher

Delft, The Netherlands & East Lansing, MI, U.S.A.

- A Joint collaboration with Technische Universiteit Delft and Michigan State University involving the development of computational models of various physical systems to model interactions of materials and optimize employed techniques.
- Jenoptik Laser Technologies

Brighton, MI, U.S.A.

2013

Summer Intern

- Contributed in development of a user interface for laser welding machine that allows user manipulation of robotic end-arm tooling.
- Incorporated microcontroller program via interfaced electronic devices and several developed algorithms to analyze physical data and feedback in real-time.

Selected Publications

- 1. "High Performance WSe₂ Phototransistors with 2D/2D Ohmic Contacts." Tianjiao Wang, Kraig Andrews, Arthur Bowman, Tu Hong, Michael Koehler, Jiaqiang Yan, David Mandrus, Zhixian Zhou, and Ya-Qiong Xu.
- 2. ""
- 3. ""

Selected Presentations

- 1. "Palladium Diselenide as a New Two-Dimensional Electronic Material Beyond Silicon." Kraig Andrews, Arthur Bowman, Upendra Rijal, Amanda Haglund, David Mandrus, and Zhixian Zhou. Society of Vacuum Coaters TechCon, Orlando, FL. May 2018.
- 2. "Improved On-Off in Ratio Black Phosphorus Field-Effect Transistors with True Ohmic Contacts." Kraig Andrews, Arthur Bowman, Upendra Rijal, Michael Koehler, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 3. "High Mobility Palladium Diselenide Field-Effect Transistors Using Heaving n—Doped Graphene Contacts." Arthur Bowman, **Kraig Andrews**, Upendra Rijal, Amanda Haglund, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 4. "Measuring the Barrier Height at Transition Metal Dichalcogenide Heterojunctions." Upendra Rijal, Arthur Bowman, Kraig Andrews, Michael Koehler, David Mandrus, and Zhixian Zhou. APS March Meeting, Los Angeles, CA. March 2018.
- 5. "High-Performance Top-Gated WSe₂ Transistors with Two-Dimensional Ohmic Contacts." **Kraig Andrews**, Upendra Rijal, Arthur Bowman, Hsun-Jen Chuang, Sagar Paduel, Michael Koehler, David Mandrus, and Zhixian Zhou. 41st Annual Symposium American Vacuum Society- Michigan Chapter, Ann Arbor, MI. May 2017.
- 6. "Substrate Dependence of Hall and Field-Effect Mobilities in Few-Layer MoS₂ Field-Effect Transistors." Bhim Chamlagain, Perera Meeghage, Hsun-Jen Chuang, Arthur Bowman, Upendra Rijal, **Kraig Andrews**, Joseph Klesko, Charles Winter, and Zhixian Zhou. APS March Meeting, Boston, MA, March 2016.

Teaching Experience

Teaching Assistant, Wayne State University Teaching Assistant, Michigan State University Autumn 2014 – Winter 2018 Winter 2012 – Winter 2014

Core Technical Skills

Nanofabrication: Atomic force microscopy (AFM), Electron beam lithography, Photolithography, Scanning electron microscopy (SEM), General clean room abilities (> 1000 hours), Physical vapor deposition (PVD), Electron beam deposition, Plasma etching, Reactive ion etching (RIE)

Languages & Software: C++, Fortran, Java, JavaScript, LaTeX, Python, shell script, Microsoft Office, Matlab, Mathematica

Operating Systems: OS X, Linux OS, Microsoft Windows